DEVELOPMENT OF A PVD-BASED MANUFACTURING PROCESS OF MONOLITHIC LEU IRRADIATION TARGETS FOR ⁹⁹MO PRODUCTION

FORSCHUNG-NEUTRONENQUELLE HEINZ MAIER-LEIBNITZ (FRM II) TECHNISCHE UNIVERSITÄT MÜNCHEN

Tobias Hollmer 03.09.2015

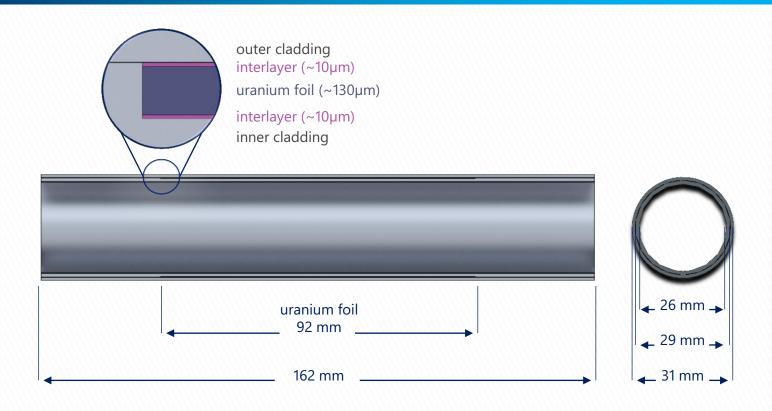


FRM II AND 99MO PRODUCTION

- FRM II:
 - Commissioning: 2004
 - Power: 20 MW
 - Max. thermal neutron flux: $8 \cdot 10^{14} \frac{n}{cm^2s}$
- Currently: installation of an irradiation facility for ⁹⁹Mo production
- Parallel: research on a next level irradiation target



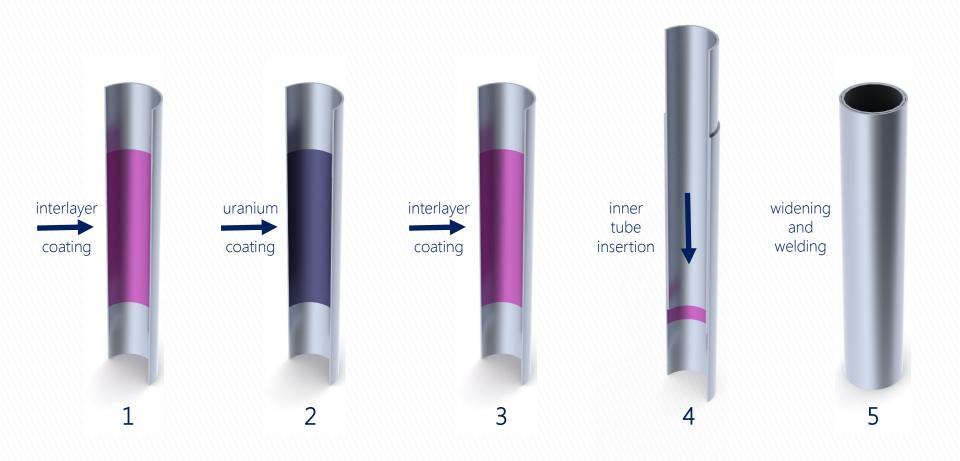
MONOLITHIC LEU TARGET



- High uranium density (HEU → LEU)
- Separability of the uranium foil (reduction of HRLW)

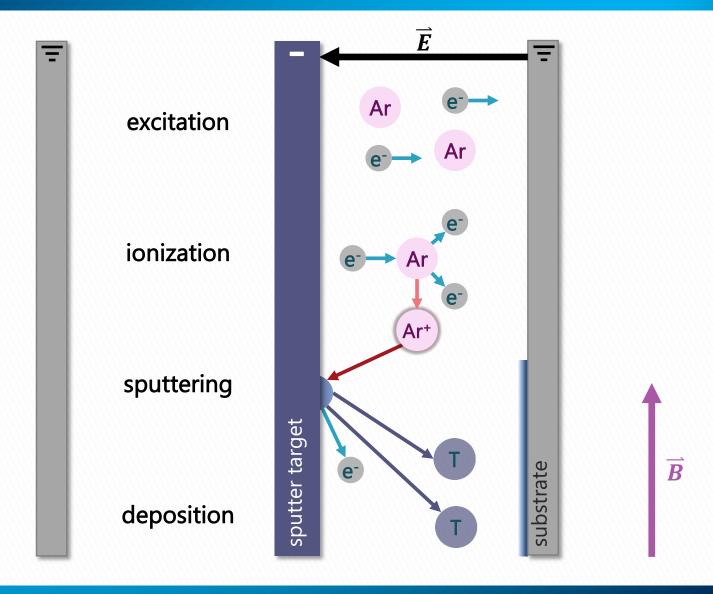


PRODUCTION PROCESS





PHYSICAL VAPOR DEPOSITION





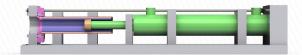
- SPUTTER TARGET PRODUCTION
- 2. COATING
- 3. ASSEMBLY



1. Sputter target production

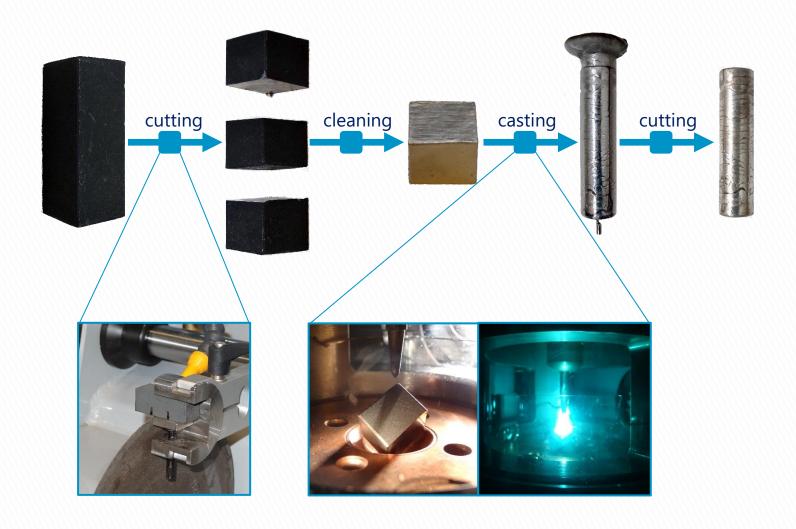


2. Coating



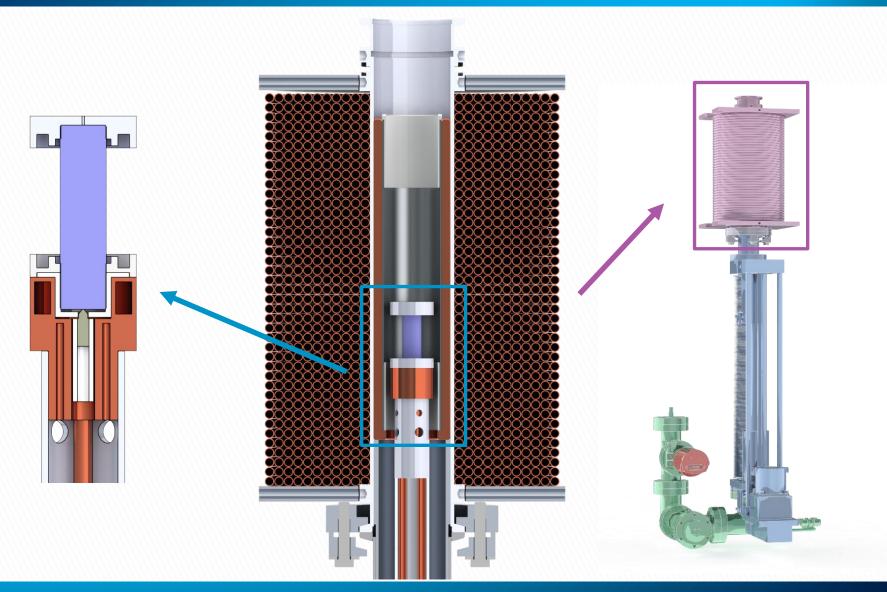
3. Assembly

- 1. Sputter target production
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COATING APPARATUS

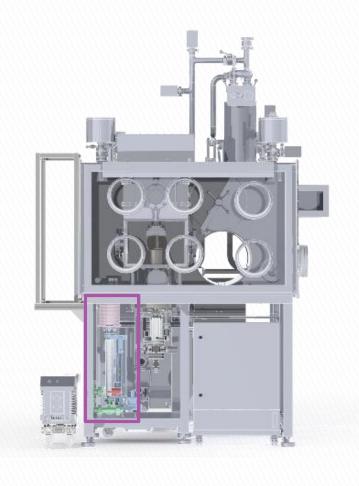
- 1. Sputter target production
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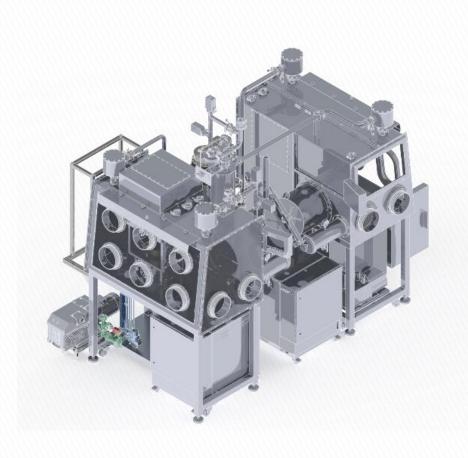




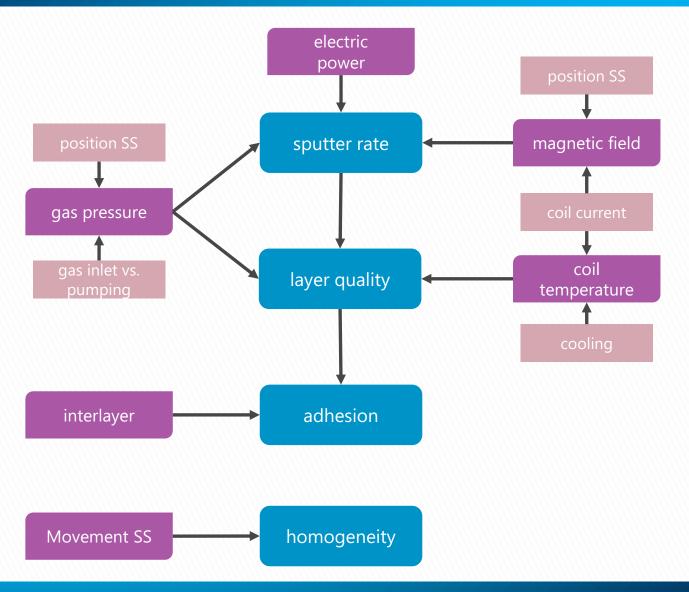
GLOVEBOX SYSTEM

- 1. Sputter target production
- 2. COATING
- 3. ASSEMBLY





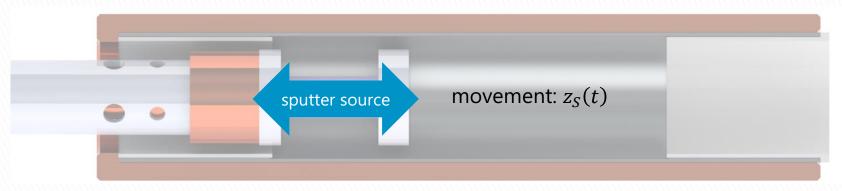
- 1. Sputter target production
- 2. COATING
- 3. ASSEMBLY



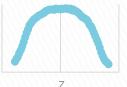


HOMOGENEITY

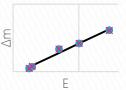
- 1. Sputter target production
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deposition characteristics: $f(z, z_S(t), Material)$

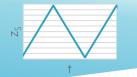


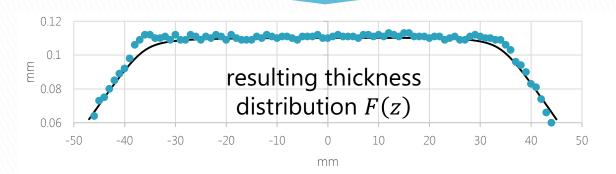
sputter rate: R(P(t), I(t), material)



coating process:

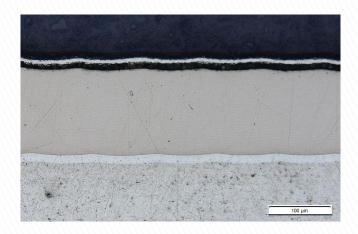
$$F(z) = C \int_0^T f(z, z_S(t)) R(t) dt$$

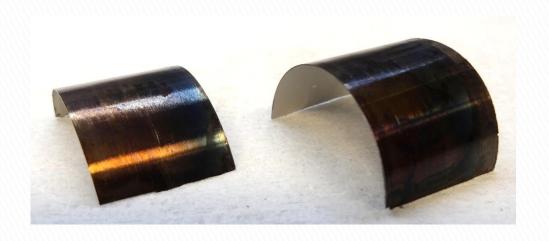




- 1. Sputter target production
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- High mechanical strength when applying high substrate temperatures (coil temperature + sputter power)
- Foils easily removable when using interlayers like graphite or aluminum

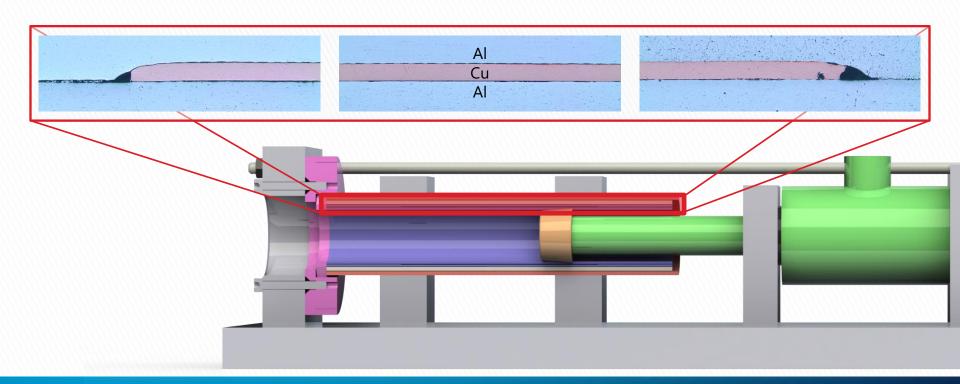






- 1. Sputter target production
- 2. COATING
- 3. ASSEMBLY

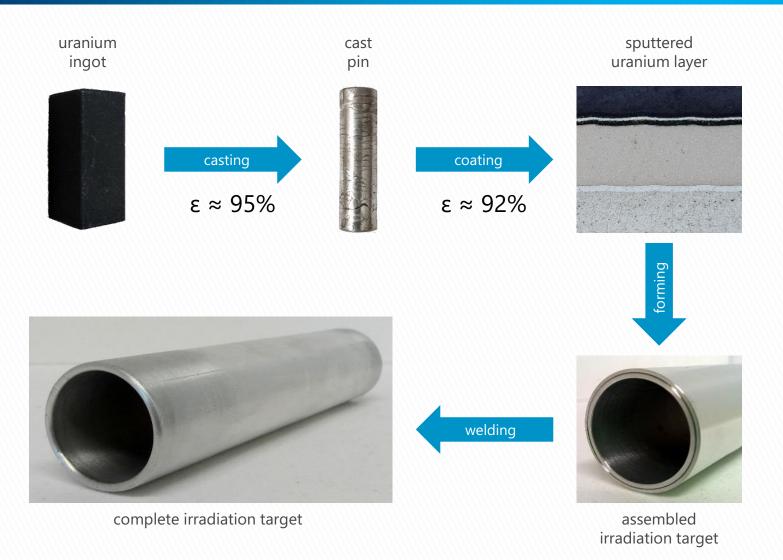
- Investigation of two different forming techniques:
 electromagnetic forming and hydraulic forming
- Successful demonstration of forming irradiation targets with sputtered foils





SUMMARY

- . Sputter target production
- 2. COATING
- 3. ASSEMBLY



Thank you for your attention!

